NISTTech

ION SOURCE AND METHOD FOR MAKING SAME

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Abstract

An embodiment of a high brightness ion source is disclosed. The high brightness ion source issued for producing a high resolution, focused ion beam with applications, e.g., in nanoscalefabrication and analysis tools for nanotechnology. Further disclosed is a method for producingthe high brightness ion source, the method including: transverse laser cooling to enhance abrightness of an ion beam. The ion source has advantageous attributes including a brightnessgreater than or equal to 107 A $m\cdot;2sr-1eV\cdot;1$ for a Ba+ beam. Consequently, the disclosed ion sourcehas a brightness value that is ten times a maximum known brightness of any conventional liquidmetal ion source.

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Status of Availability

This invention is available for licensing exclusively or non-exclusively in any field of use.

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